

In re: *Kong et al.*  
Appl. Serial No. 09/715,576  
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**Listing of Claims:**

Claims 1-21 (canceled)

Claim 22 (previously presented): A chemical vapor deposition system according to Claim 49 wherein said reaction vessel is made of quartz.

Claim 23 (canceled)

Claim 24 (previously presented): A chemical vapor deposition system according to Claim 49 wherein said source of electromagnetic radiation comprises an induction coil surrounding said reaction vessel.

Claims 25-48 (canceled)

Claim 49 (currently amended): A chemical vapor deposition system consisting essentially of:

a reactor reaction vessel formed of a material substantially transparent to electromagnetic radiation;  
a gas supply system in fluid communication with said reactor reaction vessel;  
a source of electromagnetic radiation external to said reaction vessel; and  
a susceptor within said reaction vessel, ~~and~~ said susceptor formed of a material that is thermally responsive to electromagnetic radiation, wherein said susceptor ~~being an inverted truncated cone~~ is defined by a plurality of adjacent straight sidewall sections forming a hollow inverted truncated cone with and a plurality of wafer pockets on the inner circumference of said truncated cone, with and wherein the spacing between facing walls sidewall sections is unobstructed and so dimensioned that ~~being small enough for~~ said facing walls sidewall sections to radiantly heat the exposed face surface of a facing

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substrate wafer to substantially the same temperature as said susceptor portion heats a substrate wafer that is in one of said wafer pockets to thereby minimize or substantially eliminate radial and axial temperature gradients across a substrate wafer.

Claim 50 (previously presented): A chemical vapor deposition system according to Claim 49 wherein said susceptor is formed from graphite coated with silicon carbide.